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Gleim et al.

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[54] POSITIVE PHOTORESISTS CONTAINING PREFORMED POLYGLUTARIMIDE POLYMER

[75] Inventors: **Robert D. Gleim**, Newtown; **Mark P. de Grandpre**, Ambler, both of Pa.

[73] Assignee: **Rohm and Haas Company**, Philadelphia, Pa.

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[52] **U.S. Cl.** **430/176**; 430/156; 430/192; 430/270; 430/313; 430/326

[58] **Field of Search** 430/192, 270, 156, 326, 430/313, 176

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Primary Examiner—John E. Kittle
Assistant Examiner—Mukund J. Shah
Attorney, Agent, or Firm—Marc S. Adler

[57] **ABSTRACT**

This invention relates to a positive photoresist system possessing a high degree of thermal stability. The photoresist system contains a preformed polyglutarimide polymer dissolved in a non-reacting solvent. The positive resist is capable of achieving high resolution images by exposure to a wide range of wavelengths and development using an aqueous base developer. The photoresist system is also suitable for use as a planarizing layer in a multiple layer system.

30 Claims, No Drawings